

INFORMATION DISCLOSURE STATEMENT

BY APPLICANT

Docket: 6047-53173

App: 09/590,795

Applicant: Vishnu K. Agarwal et al.

Filed: June 8, 2000

Art Unit:

U.S. PATENT DOCUMENTS

Init.*		Number	Date	Name	Class	Sub	Filed
DV		6,060,367	5/9/00	Sze			
		6,060,351	5/9/00	Parekh et al.			
		6,049,101	4/11/00	Graettinger et al.			
		6,037,220	3/14/00	Chien et al.			
		6,015,743	1/18/00	Zahurak et al.			
		5,962,065	10/5/99	Weimer et al.			
		5,985,714	11/16/99	Sandhu et al.			
		5,959,327	9/28/99	Sandhu et al.			
		5,877,063	3/2/99	Gilchrist			
		5,696,014	12/9/97	Figura			
		5,612,560	3/18/97	Chivukula et al.			
		5,608,247	3/4/97	Brown			
		5,427,974	6/27/95	Lur et al.			
		5,372,962	12/13/94	Hirota et al.			
		5,342,800	8/30/94	Jun			
DV		5,318,920	6/7/94	Hayashide			

EXAMINER:

ghuland

DATE 09/24/02

*Examiner: Initial if considered, whether or not in conformance with MPEP 60;
draw line through cite if not in conformance and not considered. Send copy.

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Docket: 6047-53173	App: 09/590,795
	Applicant: Vishnu K. Agarwal et al.	
	Filed: June 8, 2000	Art Unit:

U.S. PATENT DOCUMENTS

Init.*		Number	Date	Name	Class	Sub	Filed
DV		5,130,885	7/14/92	Fazan et al.	_____	_____	
DV		5,068,199	11/26/91	Sandhu	_____	_____	

FOREIGN PATENT DOCUMENTS

		Number	Date	Country	Class	Sub	

OTHER DOCUMENTS

DV			Kawahara, Takaaki et al., "(Ba, Sr)TiO ₃ Films Prepared by Liquid Source Chemical Vapor Deposition on Ru Electrodes," <u>Jpn. J. Appl. Phys.</u> , 35:4880-4885 (1996).

EXAMINER: <i>ghickland</i>	DATE 09/24/02
----------------------------	---------------

*Examiner: Initial if considered, whether or not in conformance with MPEP 60; draw line through cite if not in conformance and not considered. Send copy.

COPY OF PAPERS
ORIGINALLY FILEDINFORMATION DISCLOSURE
STATEMENT

BY APPLICANT

~~Docket: 6047-61467~~

App: 10/002,906

Applicant: Agarwal et al.

Filed: October 29, 2001

Art Unit:

U.S. PATENT DOCUMENTS

Init.*		Number	Date	Name	Class	Sub	Filed
DV		5,852,307	12/22/98	Aoyama et al.			

FOREIGN PATENT DOCUMENTS

		Number	Date	Country	Class	Sub	

OTHER DOCUMENTS

DV			Kaga et al., "Thermal Stability of RUO2 Thin Films and Effects of Annealing Ambient on Their Reduction Process," <u>Jpn. J. Appl. Phys.</u> , 38:3689-3692 (1999).
DV			Hayashide et al., "Fabrication of Storage Capacitance-Enhanced Capacitors with a Rough Electrode," <u>Japanese Jpn. J. Appl. Phys.</u> , pp. 869-872 (1990).
DV			Matsui et al., "Thermal Stability of a RUO2 Electrode Prepared by DC Reactive Sputtering," <u>Jpn. J. Appl. Phys.</u> , 39:256-263 (2000).

EXAMINER: *ghilard*

DATE 09/24/02

*Examiner: Initial if considered, whether or not in conformance with MPEP 609; draw line through cite if not in conformance and not considered. Send copy.